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(71)Applicant: TEKTRONIX INC

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(72)Inventor: HINCHLIFFE ROBERT D

KEPHART DONALD E

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(54) BATH FOR ELECTROPHORETIC DEPOSITION AND DEPOSITION METHOD

(57) Abstract:

PROBLEM TO BE SOLVED: To provide the bath for electroporetic deposition which is suitable for the manufacture of an electrode structure capable of reducing a current supplied to plasma while the sputtering of an electrode is reduced by allowing the bath for electrophoretic deposition to contain magnesium nitrate of specific concn.

SOLUTION: The current supplied to the plasma of a PALC display panel depends upon the concn. of magnesium nitrate in the bath for electrophoretic deposition and the concn. of the magnesium nitrate for forming a sufficient coating of LaB6 is about 2×10-5 mol. Namely, salt as an assistant of about (n/2)×2×10-5 mol in concn. is used for the electrophoretic depositon method using a solution containing rare earth boride and then a metallic body can be provided with a sufficient coating of rare earth boride. When this coated metallic body is used as the cathode of the PALC display panel, the value of the current supplied to the plasma is reducible.

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